

Title (en)
SPUTTER CHAMBER AND VACUUM TRANSPORT CHAMBER AND VACUUM TREATMENT INSTALLATIONS WITH CHAMBERS OF THIS TYPE

Title (de)
SPUTTERKAMMER SOWIE VAKUUMTRANSPORTKAMMER UND VAKUUMBEHANDLUNGSANLAGEN MIT SOLCHEN KAMMERN

Title (fr)
CHAMBRE A PULVERISATION CATHODIQUE ET CHAMBRE DE TRANSPORT A VIDE, ET INSTALLATIONS DE TRAITEMENT DU VIDE COMPORTANT DES CHAMBRES DE CE TYPE

Publication
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Application
EP 01900067 A 20010112

Priority
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• CH 912000 A 20000118

Abstract (en)
[origin: WO0153561A1] A substrate support (5) is mounted in a sputter chamber in such a way that said support can be driven in rotation about an axis (A). A magnetron source is mounted in the sputter chamber with a central axis (Z) inclined (beta) towards the axis of rotation of the substrate support (5).

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C23C 14/35; **C23C 14/56**

IPC 8 full level
C23C 14/22 (2006.01); **C23C 14/35** (2006.01); **C23C 14/56** (2006.01); **G11B 7/26** (2006.01)

CPC (source: EP)
C23C 14/225 (2013.01); **C23C 14/35** (2013.01); **C23C 14/566** (2013.01)

Citation (search report)
See references of WO 0153561A1

Citation (examination)
• EP 0435098 A2 19910703 - MACHINE TECHNOLOGY INC [US]
• EP 0933444 A1 19990804 - SHIBAURA MECHATRONICS CORP [JP]
• DE 69322404 T2 19990429 - ADVANCED ENERGY IND INC FORT C [US]
• JP H10147864 A 19980602 - NEC CORP
• KIYOTAKA WASA, SHIGERU HAYAKAWA: "Handbook of sputter deposition technology", 1 January 1992, NOYES PUBLICATIONS, US, ISBN: 0815512805, pages: 100 - 103

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